

10/593,746

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NEWS	4	APR 02	DWPI: New display format ALLSTR available
NEWS	5	APR 02	New Thesaurus Added to Derwent Databases for Smooth Sailing through U.S. Patent Codes
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NEWS	13	JUN 21	Removal of Pre-IPC 8 data fields streamline displays in CA/CAPLUS, CASREACT, and MARPAT
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NEWS	15	JUN 28	Introducing "CAS Chemistry Research Report": 40 Years of Biofuel Research Reveal China Now Atop U.S. in Patenting and Commercialization of Bioethanol
NEWS	16	JUN 29	Enhanced Batch Search Options in DGENE, USGENE, and PCTGEN
NEWS	17	JUL 19	Enhancement of citation information in INPADOC databases provides new, more efficient competitor analyses
NEWS	18	JUL 26	CAS coverage of global patent authorities has expanded to 61 with the addition of Costa Rica
NEWS	19	SEP 15	MEDLINE Cited References provide additional relevant records with no additional searching.
NEWS	20	OCT 04	Removal of Pre-IPC 8 data fields streamlines displays in USPATFULL, USPAT2, and USPATOLD.
NEWS	21	OCT 04	Precision of EMBASE searching enhanced with new chemical name field

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NEWS 22 OCT 06 Increase your retrieval consistency with new formats for  
Taiwanese application numbers in CA/CAplus.

NEWS EXPRESS FEBRUARY 15 10 CURRENT WINDOWS VERSION IS V8.4.2,  
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\* \* \* \* \* STN Columbus \* \* \* \* \*

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=> FILE REG		
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DICTIONARY FILE UPDATES: 18 OCT 2010 HIGHEST RN 1246494-44-9

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experimental property data in the original document. For information  
on property searching in REGISTRY, refer to:

<http://www.cas.org/support/stngen/stndoc/properties.html>

=> S 64404-02-4  
L1 0 64404-02-4

=> S SARTOMER 349

10/593,746

270 SARTOMER  
8870 349  
L2 6 SARTOMER 349  
(SARTOMER(W)349)

=> S SARTOMER 349/CRN  
L3 0 SARTOMER 349/CRN

=> S SARTOMER 349/CN  
L4 1 SARTOMER 349/CN

=> D ALL

L4 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2010 ACS on STN

RN 24447-78-7 REGISTRY

ED Entered STN: 16 Nov 1984

CN 2-Propenoic acid, 1,1'-[(1-methylethylidene)bis(4,1-phenyleneoxy-2,1-ethanediyl)] ester (CA INDEX NAME)

OTHER CA INDEX NAMES:

CN 2-Propenoic acid, (1-methylethylidene)bis(4,1-phenyleneoxy-2,1-ethanediyl) ester (9CI)

CN Acrylic acid, diester with 2,2'-[isopropylidenebis(p-phenyleneoxy)]diethanol (8CI)

CN Ethanol, 2,2'-[isopropylidenebis(p-phenyleneoxy)]di-, diacrylate (8CI)

OTHER NAMES:

CN 2,2-Bis(4-acryloxyethoxyphenyl)propane

CN 2,2-Bis[4-(2-acryloyloxyethoxy)phenyl]propane

CN Bisphenol A bis(2-hydroxyethyl ether) diacrylate

CN Bisphenol A bis[2-(acryloyloxy)ethyl] ether

CN Bisphenol A di(acryloyloxyethyl) ether

CN Bis[1-(2-acryloxy)-p-ethoxyphenyl]dimethylmethane]

CN BR 800

CN EB 952

CN FM 300

CN Kayarad FM 300

CN Sartomer 349

CN Sartomer SR 349

CN Setalin AM 548

CN Setalux UV 2246

CN Setalux UV 2248

CN SR 349

DR 58458-00-7, 130340-91-9, 143550-30-5, 208666-27-7

MF C25 H28 O6

CI COM

LC STN Files: CA, CAPLUS, CASREACT, CHEMCATS, CHEMLIST, CIN, CSCHEM, IFICDB, IFIPAT, IFIUDB, MSDS-OHS, PIRA, PROMT, TOXCENTER, USPAT2, USPATFULL, USPATOLD

Other Sources: DSL\*\*, EINECS\*\*, TSCA\*\*

(\*\*Enter CHEMLIST File for up-to-date regulatory information)

DT.CA Caplus document type: Conference; Journal; Patent; Report

RL.P Roles from patents: BIOL (Biological study); PREP (Preparation); PROC (Process); PRP (Properties); RACT (Reactant or reagent); USES (Uses)

RLD.P Roles for non-specific derivatives from patents: BIOL (Biological study); PREP (Preparation); PROC (Process); PRP (Properties); USES (Uses)

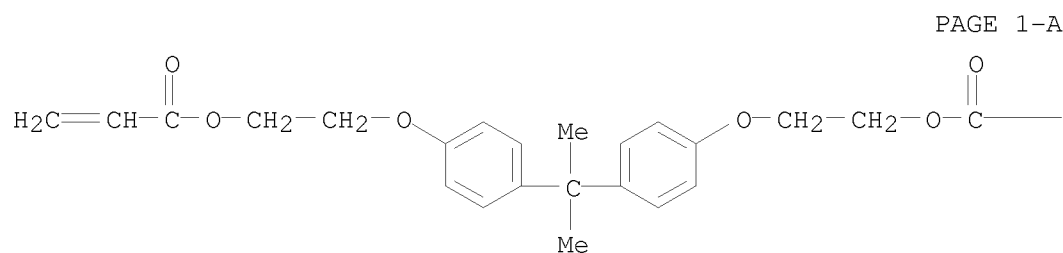
RL.NP Roles from non-patents: ANST (Analytical study); BIOL (Biological study); CMBI (Combinatorial study); OCCU (Occurrence); PREP

(Preparation); PROC (Process); PRP (Properties); RACT (Reactant or reagent); USES (Uses)

RLD.NP Roles for non-specific derivatives from non-patents: PREP (Preparation); PROC (Process); PRP (Properties); USES (Uses)

#### Ring System Data

Elemental Analysis	Elemental Sequence	Size of the Rings	Ring System Formula	Ring Identifier	RID Occurrence
EA	ES	SZ	RF	RID	Count
=====	=====	=====	=====	=====	=====
C6	C6	6	C6	46.150.18	2



—CH=CH<sub>2</sub>

#### Experimental Properties (EPROP)

PROPERTY (CODE)	VALUE	NOTE
=====	=====	=====
IR Absorption Spectra	Spectrum	(1) BIORAD

- (1) Infrared spectral data from the Bio-Rad/Sadtler IR Data Collection was obtained from Bio-Rad Laboratories, Philadelphia, PA (US). Copyright (C) Bio-Rad Laboratories. All Rights Reserved.

#### Experimental Property Tags (ETAG)

PROPERTY	NOTE
=====	=====
Viscosity	(1) CAS

- (1) Tarzi, O. I.; Journal of Polymer Science, Part A: Polymer Chemistry 2010 V48(12) P2594-2603 CAPLUS

#### Predicted Properties (PPROP)

PROPERTY (CODE)	VALUE	CONDITION	NOTE
Bioconc. Factor (BCF)	9102.35	pH 1 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 2 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 3 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 4 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 5 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 6 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 7 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 8 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 9 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 10 25 deg C	(1)
Boiling Point (BP)	554.3+/-50.0 deg C	760 Torr	(1)
Density (DEN)	1.117+/-0.06 g/cm**3	20 deg C	(1)
		760 Torr	
Enthalpy of Vap. (HVAP)	83.53+/-3.0 kJ/mol	760 Torr	(1)
Flash Point (FP)	237.4+/-30.2 deg C		(1)
Freely Rotatable Bonds (FRB)	14		(1)
H acceptors (HAC)	6		(1)
H donors (HD)	0		(1)
Hydrogen Donors/Acceptors Sum (HDAS)	6		(1)
Koc (KOC)	23743.88	pH 1 25 deg C	(1)
Koc (KOC)	23743.88	pH 2 25 deg C	(1)
Koc (KOC)	23743.88	pH 3 25 deg C	(1)
Koc (KOC)	23743.88	pH 4 25 deg C	(1)
Koc (KOC)	23743.88	pH 5 25 deg C	(1)
Koc (KOC)	23743.88	pH 6 25 deg C	(1)
Koc (KOC)	23743.88	pH 7 25 deg C	(1)
Koc (KOC)	23743.88	pH 8 25 deg C	(1)
Koc (KOC)	23743.88	pH 9 25 deg C	(1)
Koc (KOC)	23743.88	pH 10 25 deg C	(1)
LOGD (LOGD)	5.51	pH 1 25 deg C	(1)
LOGD (LOGD)	5.51	pH 2 25 deg C	(1)
LOGD (LOGD)	5.51	pH 3 25 deg C	(1)
LOGD (LOGD)	5.51	pH 4 25 deg C	(1)
LOGD (LOGD)	5.51	pH 5 25 deg C	(1)
LOGD (LOGD)	5.51	pH 6 25 deg C	(1)
LOGD (LOGD)	5.51	pH 7 25 deg C	(1)
LOGD (LOGD)	5.51	pH 8 25 deg C	(1)
LOGD (LOGD)	5.51	pH 9 25 deg C	(1)
LOGD (LOGD)	5.51	pH 10 25 deg C	(1)
LOGP (LOGP)	5.512+/-0.377	25 deg C	(1)
Mass Intrinsic Solubility (ISLB.MASS)	0.0016 g/L	25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 1 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 2 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 3 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 4 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 5 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 6 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 7 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 8 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 9 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 10 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	Unbuffered Water	(1)
		pH 7.00	

Molar Intrinsic Solubility (ISLB.MOL)	0.0000038 mol/L	25 deg C	
		25 deg C	(1)
Molar Solubility (SLB.MOL)	0.0000038 mol/L	pH 1 25 deg C	(1)
Molar Solubility (SLB.MOL)	0.0000038 mol/L	pH 2 25 deg C	(1)
Molar Solubility (SLB.MOL)	0.0000038 mol/L	pH 3 25 deg C	(1)
Molar Solubility (SLB.MOL)	0.0000038 mol/L	pH 4 25 deg C	(1)
Molar Solubility (SLB.MOL)	0.0000038 mol/L	pH 5 25 deg C	(1)
Molar Solubility (SLB.MOL)	0.0000038 mol/L	pH 6 25 deg C	(1)
Molar Solubility (SLB.MOL)	0.0000038 mol/L	pH 7 25 deg C	(1)
Molar Solubility (SLB.MOL)	0.0000038 mol/L	pH 8 25 deg C	(1)
Molar Solubility (SLB.MOL)	0.0000038 mol/L	pH 9 25 deg C	(1)
Molar Solubility (SLB.MOL)	0.0000038 mol/L	pH 10 25 deg C	(1)
Molar Solubility (SLB.MOL)	0.0000038 mol/L	Unbuffered Water	(1)
		pH 7.00	
		25 deg C	
Molar Volume (MVOL)	379.9+/-3.0 cm**3/mol	20 deg C	(1)
		760 Torr	
Molecular Weight (MW)	424.49		(1)
Polar Surface Area (PSA)	71.06 A**2		(1)
Vapor Pressure (VP)	2.51E-12 Torr	25 deg C	(1)

(1) Calculated using Advanced Chemistry Development (ACD/Labs) Software V11.02  
((C) 1994-2010 ACD/Labs)

See HELP PROPERTIES for information about property data sources in REGISTRY.

204 REFERENCES IN FILE CA (1907 TO DATE)

27 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA

205 REFERENCES IN FILE CAPLUS (1907 TO DATE)

#### REFERENCE 1

AN 153:383443 CA  
 TI Visible light photoinitiating systems: toward a good control of the photopolymerization efficiency  
 AU Ibrahim, A.; Ley, C.; Tarzi, O. I.; Fouassier, J. P.; Allonas, X.  
 CS Department of Photochemistry, CNRS, ENSCMu, University of Haute Alsace, Mulhouse, 68093, Fr.  
 SO Journal of Photopolymer Science and Technology (2010), 23(1), 101-108  
 CODEN: JSTEEW; ISSN: 0914-9244  
 PB Conference of Photopolymer Science and Technology  
 DT Journal  
 LA English  
 CC 35-4 (Chemistry of Synthetic High Polymers)  
 Section cross-reference(s): 36, 41, 67, 74  
 AB This paper discusses the photochem. of three-component photoinitiating systems (3K-PIS) for free radical photopolymn. and the efforts made during the last decades to propose efficient systems applied to the laser imaging area. A special focus is devoted to a new 3K-PIS working in the green region. It is based on a pyrromethene dye which is reduced or oxidized by a coinitiator. A third redox component is used that leads to the recovery of the initial dye and the formation of addnl. initiating species, preventing a fast photobleaching of the dye. The beneficial effect on the photopolymn. rates and the final monomer conversion is clearly noticed. Laser flash photolysis was used to understand the reaction mechanisms, and detailed photopolymn. kinetics allow the study of polymeric network

formation.

ST visible light photopolymer efficiency

IT Polymerization  
(photochem., radical; visible light photoinitiating systems, photopolymer. efficiency, and kinetics study)

IT Catalysts  
(photochem.; visible light photoinitiating systems, photopolymer. efficiency, and kinetics study)

IT Dyes  
(pyrromethene; visible light photoinitiating systems, photopolymer. efficiency, and kinetics study)

IT Fluorescence  
Polymer networks  
Polymerization kinetics  
(visible light photoinitiating systems, photopolymer. efficiency, and kinetics study)

IT 131083-16-4, 1,3,5,7,8-Pentamethyl-2,6-diethylpyrromethene-difluoroborate  
RL: CAT (Catalyst use); RCT (Reactant); RACT (Reactant or reagent); USES (Uses)  
(EMP, photosensitizer dye, initiator; visible light photoinitiating systems, photopolymer. efficiency, and kinetics study)

IT 103-01-5, N-Phenylglycine  
RL: CAT (Catalyst use); RCT (Reactant); RACT (Reactant or reagent); USES (Uses)  
(NPG, electron donor, coinitiator; visible light photoinitiating systems, photopolymer. efficiency, and kinetics study)

IT 3584-23-4, 2-(4-Methoxyphenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine  
RL: CAT (Catalyst use); RCT (Reactant); RACT (Reactant or reagent); USES (Uses)  
(TA, electron acceptor, coinitiator; visible light photoinitiating systems, photopolymer. efficiency, and kinetics study)

IT 24447-78-7, SR 349  
RL: PRP (Properties); RCT (Reactant); RACT (Reactant or reagent)  
(visible light photoinitiating systems, photopolymer. efficiency, and kinetics study)

IT 58738-89-9P, SR 349 homopolymer  
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)  
(visible light photoinitiating systems, photopolymer. efficiency, and kinetics study)

RE.CNT 37 THERE ARE 37 CITED REFERENCES AVAILABLE FOR THIS RECORD

- (1) Allonas, X; Eur Polym J 2001, V37, P897 CAPLUS
- (2) Allonas, X; Helv Chim Acta 2001, V84, P2577 CAPLUS
- (3) Allonas, X; Lasers in Chemistry, Influencing Matter 2008, V2 CAPLUS
- (4) Allonas, X; Photochem Photobiol Sci 2003, V2, P224 CAPLUS
- (5) Allonas, X; Polymer 2001, V42, P7627 CAPLUS
- (6) Andrzejewska, E; Prog Polym Sci 2001, V26, P605 CAPLUS
- (7) Anon; Photochemistry and UV curing: New trends 2006
- (8) Anseth, K; Macromolecules 1994, V27, P650 CAPLUS
- (9) Anseth, K; Macromolecules 1995, V28, P2491 CAPLUS
- (10) Anseth, K; Macromolecules 1995, V28, P4040 CAPLUS
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- (27) Kurdikar, D; Macromolecules 1994, V27, P4084 CAPLUS
- (28) Lovestead, T; Polymer 2005, V46, P6226 CAPLUS
- (29) Monroe, B; Chem Rev 1993, V93, P435 CAPLUS
- (30) Oster, G; Chem Rev 1968, V68, P125 CAPLUS
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- (32) Suzuki, S; J Photochem Photobiol A: Chem 2006, V181, P181
- (33) Tarzi, O; J Polym Sci, Part A: Polym Chem, under press
- (34) Tulig, T; Macromolecules 1981, V14, P1501 CAPLUS
- (35) Wen, M; Macromolecules 2000, V33, P9247 CAPLUS
- (36) Zhu, Q; J Photochem Photobiol, A 1991, V59, P255 CAPLUS
- (37) Zhu, S; Macromolecules 1990, V23, P1144 CAPLUS

## REFERENCE 2

AN 153:296099 CA  
 TI Multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives  
 IN Ragain, James C., Jr.; Tiba, Amer; Charlton, David G.  
 PA The United States of America Dept. of Navy, USA  
 SO U.S. Pat. Appl. Publ., 9pp.  
 CODEN: USXXCO  
 DT Patent  
 LA English  
 INCL 523118000; 433228100  
 IPCI A61K0006-00 [I,A]; A61C0005-00 [I,A]  
 NCL 523/118.000; 433/228.100  
 CC 63-7 (Pharmaceuticals)  
 Section cross-reference(s): 38  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-----	----	-----	-----	-----
PI	US 20100197825	A1	20100805	US 2009-362622	20090130
PRAI	US 2009-362622		20090130		

AB This invention describes an adhesive used for bonding dental and medical biomaterials to hard tissues via a mol. bridge formed from calcium-reactive amines and acrylic or methacrylic ester monomers to hard tissues such as enamel, dentin, and bone. This formulation consists of an acid-stable polymerizable compound with multifunctional acrylate crosslinkers. This formula provides good self-adherence without prior preparation of the hard tissue substrates. The formulation can contain chemical- and/or light-activated free radical initiators.  
 ST multifunctional acrylate crosslinker dental biomedical adhesive  
 IT Dental materials and appliances  
 Medical goods  
 (adhesives; multifunctional acrylates used as crosslinkers in dental



- and biomedical self-etching bonding adhesives)
- IT Dental materials and appliances  
(alloys; multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
- IT Dental materials and appliances  
(cements; multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
- IT Dental materials and appliances  
(ceramics; multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
- IT Dental materials and appliances  
(composites; multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
- IT Adhesives  
(medical adhesives; multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
- IT Crosslinking agents  
Polymerization catalysts  
(multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
- IT Amines  
RL: RCT (Reactant); THU (Therapeutic use); BIOL (Biological study); RACT (Reactant or reagent); USES (Uses)  
(multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
- IT 94-36-0, Benzoyl peroxide, biological studies 10373-78-1, Camphorquinone 75980-60-8, Diphenyl(2,4,6-trimethylbenzoyl)phosphine oxide  
RL: CAT (Catalyst use); THU (Therapeutic use); BIOL (Biological study); USES (Uses)  
(multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
- IT 97-63-2, Ethyl methacrylate 97-90-5, Ethylene glycol dimethacrylate 106-90-1, Glycidyl acrylate 106-91-2, Glycidyl methacrylate 109-16-0, Triethylene glycol dimethacrylate 140-88-5, Ethyl acrylate 619-84-1, 4-Dimethylaminobenzoic acid 689-12-3, Isopropyl acrylate 818-61-1, 2-Hydroxyethyl acrylate 925-60-0, Propyl acrylate 1070-70-8, 1,4-Butanediol diacrylate 1189-08-8, 1,3-Butanediol dimethacrylate 1565-94-2 1565-94-2, Bisigma 1830-78-0 1985-51-9, Neopentyl glycol dimethacrylate 2082-81-7, 1,4-Butanediol dimethacrylate 2210-28-8, Propyl methacrylate 2223-82-7, Neopentyl glycol diacrylate 2274-11-5, Ethylene glycol diacrylate 2399-48-6, Tetrahydrofurfuryl acrylate 2455-24-5, Tetrahydrofurfuryl methacrylate 3253-39-2 3253-41-6, Pentaerythritol tetramethacrylate 3290-92-4, Trimethylolpropane trimethacrylate 3524-66-1, Pentaerythritol trimethacrylate 3524-68-3, Pentaerythritol triacrylate 4491-03-6, biological studies 4655-34-9, Isopropyl methacrylate 4687-94-9 4986-89-4, Pentaerythritol tetracrylate 6606-59-3, 1,6-Hexanediol dimethacrylate 10287-53-3, Edmab 13048-33-4, 1,6-Hexanediol diacrylate 15625-89-5, Trimethylolpropane triacrylate 19485-03-1, 1,3-Butanediol diacrylate 24447-78-7 24448-20-2, biological studies 25584-83-2, Hydroxypropyl acrylate 25852-47-5, Polyethylene glycol dimethacrylate 26570-48-9, Polyethylene glycol diacrylate 26846-58-2, Pentaerythritol dimethacrylate 27689-12-9, biological studies 30206-34-9, Dipentaerythritol tetramethacrylate 32435-46-4, Bis[2-(methacryloyloxy)ethyl] phosphate 50853-28-6, Glycerol monomethacrylate 51989-01-6 52174-50-2, Glycerol diacrylate 52357-34-3, Glycerol monoacrylate 53417-29-1, Pentaerythritol diacrylate

56361-55-8, biological studies 56744-60-6 60506-81-2, SR399  
 92738-89-1, Dipentaerythritol trimethacrylate 215116-26-0,  
 Dipentaerythritol dimethacrylate  
 RL: RCT (Reactant); THU (Therapeutic use); BIOL (Biological study); RACT  
 (Reactant or reagent); USES (Uses)  
 (multifunctional acrylates used as crosslinkers in dental and  
 biomedical self-etching bonding adhesives)

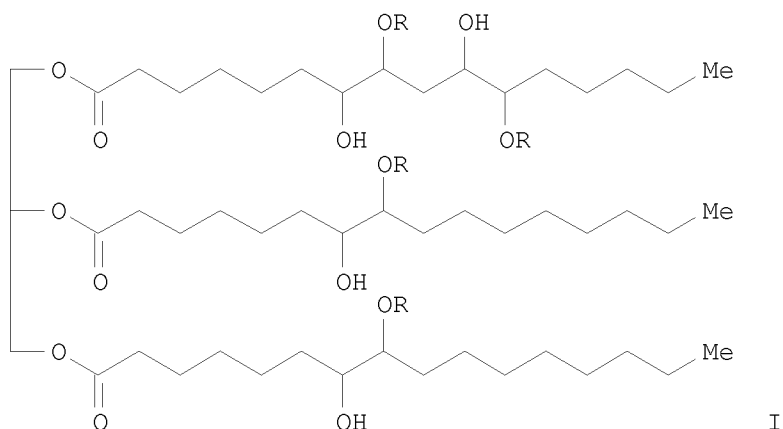
## REFERENCE 3

AN 153:236145 CA  
 TI Chemical tagging indicators for identification of overheated places in  
 power transformers  
 AU Shapovalov, L.; Figovsky, O.; Trossman, A.; Birukova, O.; Shkolnik, A.  
 CS Polymate Ltd - INRC, Migdal-HaEmek, Israel  
 SO Scientific Israel--Technological Advantages (2010), 12(1,2), 120-127  
 CODEN: SITAFG; ISSN: 1565-1533  
 PB Polymate Ltd., Israeli Research Center  
 DT Journal  
 LA English  
 CC 48-5 (Unit Operations and Processes)  
 Section cross-reference(s): 47  
 AB The purpose of this article is to develop chemical indicators for  
 identification of overheated places in power transformer with mineral oil.  
 The chemical indicators, which are suitable to be placed on potential trouble  
 spots, and release specific substances when exposed to predefined temps.  
 and allow early diagnostics and identification. It was elaborated  
 copolymers of methacrylic esters as chemical indicators in power transformers  
 with mineral oil. The indicators are not soluble in mineral oil.  
 Decomposition  
 of network copolymers gives high yields of methacrylate monomer (85-95%).  
 The monomers in mineral oil are determined by gas chromatograph. A sample of  
 scheme of card of applying indicators is recommended for industrial power  
 transformers.  
 ST power transformer mineral oil overheating identification chem tagging  
 indicator; methacrylic ester copolymer indicator power transformer oil  
 overheating  
 IT Transformer oils  
 (chemical tagging indicators for identification of overheated places in  
 power transformers)  
 IT Heating  
 (over-heating; chemical tagging indicators for identification of  
 overheated places in power transformers)  
 IT 60-00-4, reactions 80-15-9, Cumenehydroperoxide 80-43-3,  
 Dicumylperoxide 94-36-0, Dibenzoyl peroxide, reactions 97-63-2, Ethyl  
 methacrylate 97-86-9, Isobutyl methacrylate 97-88-1, Butyl  
 methacrylate 99-97-8, N,N-Dimethyl-p-toluidine 105-64-6 1338-23-4,  
 Methyl ethyl ketoneperoxide 2867-47-2, Dimethylaminoethyl methacrylate  
 10373-78-1, Camphorquinone 18358-13-9, Methacrylate, reactions  
 24447-78-7, SR-349 24448-20-2, SR-348  
 RL: RCT (Reactant); RACT (Reactant or reagent)  
 (chemical tagging indicators for identification of overheated places in  
 power transformers)  
 RE.CNT 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD  
 (1) Anon; PCT/IL 2008/00224  
 (2) Anon; [www.hse.gov.uk/research/misc/sherzat/sum.pdf](http://www.hse.gov.uk/research/misc/sherzat/sum.pdf), PCT/IL 2008/00224  
 (3) Bamford, C; Comprehensive chemical kinetics P53

## REFERENCE 4

AN 153:206507 CA  
 TI Acryloyl-containing coating compositions with good hardness, adhesion, transparency, and chemical resistance  
 IN Lee, Seong Gwon; Lee, Jeong Beom; Park, Sang Gwon  
 PA EP Chemtech Co., Ltd., S. Korea  
 SO Repub. Korean Kongkae Taeho Kongbo, 16pp.  
 CODEN: KRXXA7  
 DT Patent  
 LA Korean  
 IPCI C08L0033-08 [I,A]; C08L0033-00 [I,C\*]; C08K0003-20 [I,A]; C08K0003-00 [I,C\*]; C08K0005-54 [I,A]; C08K0005-00 [I,C\*]; C09D0133-08 [I,A]  
 CC 42-7 (Coatings, Inks, and Related Products)  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-----	---	-----	-----	-----
PI	KR 2010072566	A	20100701	KR 2008-131004	20081222
PRAI	KR 2008-131004	20081222			
GI					



AB Title coating compns. comprise (A) an acrylate monomer synthesized from a polyol (I) and an acrylic monomer, (B) an acrylic monomer, (3) an inorg. oxide, and (D) a silane coupling agent, wherein R = H or hydrocarbon.  
 ST acryloyl contg coating compn hardness adhesion transparency chem resistance  
 IT Polyurethanes  
 RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)  
 (acrylates, polymers with vegetable oil acrylate; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)  
 IT Antistatic agents  
 (acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)  
 IT Soybean oil  
 RL: RCT (Reactant); RACT (Reactant or reagent)

- (acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)
- IT Electric conductors  
(antistatic agent; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)
- IT Alkali metal salts  
Quaternary ammonium compounds  
RL: MOA (Modifier or additive use); USES (Uses)  
(antistatic agent; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)
- IT Coating materials  
(antistatic; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)
- IT Coating materials  
(chemical resistant; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)
- IT Transparent materials  
(coatings; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)
- IT Soybean oil  
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(epoxidized, acrylate, polymers with acrylic monomers; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)
- IT Coating materials  
(transparent; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)
- IT 920-46-7DP, Methacrylic chloride, reaction products with epoxidized soybean oil 26570-48-9DP, Polyethylene glycol diacrylate, polymers with epoxidized soybean oil acrylate  
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)
- IT 1070-70-8D, polymers with vegetable oil acrylate 1680-21-3D, Triethylene glycol diacrylate, polymers with vegetable oil acrylate 2223-82-7D, Neopentyl glycol diacrylate, polymers with vegetable oil acrylate 3524-68-3D, Pentaerythritol triacrylate, polymers with vegetable oil acrylate 4986-89-4D, Pentaerythritol tetraacrylate, polymers with vegetable oil acrylate 13048-33-4D, 1,6-Hexanediol diacrylate, polymers with vegetable oil acrylate 15625-89-5D, Trimethylolpropane triacrylate, polymers with vegetable oil acrylate 24447-78-7D, polymers with vegetable oil acrylate 29570-58-9D, Dipentaerythritol hexaacrylate, polymers with vegetable oil acrylate 42978-66-5D, Tripropylene glycol diacrylate, polymers with vegetable oil acrylate 57472-68-1D, Dipropylene glycol diacrylate, polymers with vegetable oil acrylate 60506-81-2D, Dipentaerythritol pentaacrylate, polymers with vegetable oil acrylate 94108-97-1D, Ditrimehylolpropane tetraacrylate, polymers with vegetable oil acrylate 115633-58-4D, Ditrimehylolpropane triacrylate, polymers with vegetable oil acrylate  
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)  
(acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

IT 7601-89-0, Sodium perchlorate 7791-03-9, Lithium perchlorate  
 126213-51-2, Poly(3,4-ethylenedioxythiophene) 473797-97-6, Baytron PH  
 RL: MOA (Modifier or additive use); USES (Uses)  
 (antistatic agent; acryloyl-containing coating compns. with good hardness,  
 adhesion, transparency, and chemical resistance)

## REFERENCE 5

AN 153:175274 CA  
 TI Pyrromethene derivatives in three-component photoinitiating systems for  
 free radical photopolymerization  
 AU Tarzi, O. I.; Allonas, X.; Ley, C.; Fouassier, J.-P.  
 CS CIHIDECAR-CONICET, Department of Organic Chemistry, FCEyN-University of  
 Buenos Aires, Pabellon 2--Ciudad Universitaria, Buenos Aires, 1428,  
 Argent.  
 SO Journal of Polymer Science, Part A: Polymer Chemistry (2010), 48(12),  
 2594-2603  
 CODEN: JPACEC; ISSN: 0887-624X  
 PB John Wiley & Sons, Inc.  
 DT Journal  
 LA English  
 CC 35-3 (Chemistry of Synthetic High Polymers)  
 AB 1,3,5,7,8-Pentamethyl pyrromethene difluoroborate complex (HMP) and  
 2,6-diethyl-8-phenyl-1,3,5,7-tetramethylpyrromethene difluoroborate  
 complex (EPP) were used to initiate the polymerization of a diacrylate in a  
 two- and a three-component photoinitiating system (PIS), together with an amine  
 (ethyl-4-dimethylaminobenzoate, EDB) and triazine A  
 (2-(4-methoxyphenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine, TA) as  
 coinitiators. For both pyrromethene dyes, the highest conversion was  
 achieved with the three-component PIS. As these dyes have  
 high-fluorescence quantum yields, steady state and time-resolved  
 techniques were used to study the possible fluorescence quenching by the  
 amine and the triazine, as well as laser flash photolysis to investigate  
 the electron transfer process that occurs in these PIS from either the  
 singlet or triplet excited states. The electron transfer reaction is  
 evidenced by using time-resolved photocond. Expts. show that the main  
 interaction between the dye and both coinitiators is through its excited  
 singlet state and the process is more efficient when TA is present. The  
 beneficial effect noted when both coinitiators are used in a  
 three-component system is ascribed to secondary reactions between the  
 coinitiators and intermediates that lead to the generation of higher amount  
 of initiating species and the recovery of the initial dye.  
 ST ethoxylated bisphenol A diacrylate radical photochem polymn catalyst  
 kinetics  
 IT Polymerization  
 Polymerization catalysts  
 Polymerization kinetics  
 (photochem., radical; pyrromethene derivs. in three-component  
 photoinitiating systems for free radical photopolymn.)  
 IT Electron transfer  
 Excited singlet state  
 Redox potential  
 (pyrromethene derivs. in three-component photoinitiating systems for  
 free radical photopolymn.)  
 IT 3584-23-4, 2-(4-Methoxyphenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine  
 10287-53-3, Ethyl-4-dimethylaminobenzoate 121207-31-6 189264-25-3

RL: CAT (Catalyst use); USES (Uses)  
 (pyrromethene derivs. in three-component photoinitiating systems for free radical photopolymer.)

IT 58738-89-9P, Sartomer SR 349 homopolymer  
 RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)  
 (pyrromethene derivs. in three-component photoinitiating systems for free radical photopolymer.)

IT 24447-78-7, Sartomer SR 349  
 RL: RCT (Reactant); RACT (Reactant or reagent)  
 (pyrromethene derivs. in three-component photoinitiating systems for free radical photopolymer.)

RE.CNT 60 THERE ARE 60 CITED REFERENCES AVAILABLE FOR THIS RECORD

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## REFERENCE 6

- AN 153:116641 CA
- TI Overcoming the oxygen inhibition in the photopolymerization of acrylates: A study of the beneficial effect of triphenylphosphine
- AU Belon, C.; Allonas, X.; Croutxe-barghorn, C.; Lalevee, J.
- CS Departement de Photochimie Generale, UMR 7525 CNRS, Ecole Nationale Supérieure de Chimie de Mulhouse, Université de Haute-Alsace, Mulhouse, 68093, Fr.
- SO Journal of Polymer Science, Part A: Polymer Chemistry (2010), 48(11), 2462-2469  
CODEN: JPACEC; ISSN: 0887-624X
- PB John Wiley & Sons, Inc.
- DT Journal
- LA English
- CC 35-3 (Chemistry of Synthetic High Polymers)
- AB Triphenylphosphine (TPP) was used in free-radical UV-curable resins to reduce oxygen inhibition effect. The relative influence of concentration, monomer viscosity, light intensity and sample thickness on TPP efficiency was investigated by real time IR spectroscopy. It is shown that TPP is an effective oxygen scavenger. The mechanism was investigated by means of Laser Flash Photolysis.
- ST acrylate photopolymer kinetics triphenylphosphine oxygen scavenger
- IT Polysiloxanes
- RL: PRP (Properties); RCT (Reactant); RACT (Reactant or reagent)  
(acrylates; overcoming oxygen inhibition in photopolymer. of acrylates using triphenylphosphine as oxygen scavenger)
- IT Polymerization kinetics  
(photochem.; overcoming oxygen inhibition in photopolymer. of acrylates using triphenylphosphine as oxygen scavenger)
- IT 75980-60-8, Diphenyl-(2,4,6-trimethylbenzoyl)-phosphine oxide  
RL: CAT (Catalyst use); USES (Uses)  
(overcoming oxygen inhibition in photopolymer. of acrylates using triphenylphosphine as oxygen scavenger)
- IT 13048-33-4 24447-78-7, Sartomer 349 42978-66-5, Tripropylene glycol diacrylate  
RL: PRP (Properties); RCT (Reactant); RACT (Reactant or reagent)

(overcoming oxygen inhibition in photopolymn. of acrylates using triphenylphosphine as oxygen scavenger)

IT 603-35-0, Triphenylphosphine, uses

RL: NUU (Other use, unclassified); USES (Uses)

(oxygen scavenger; overcoming oxygen inhibition in photopolymn. of acrylates using triphenylphosphine as oxygen scavenger)

RE.CNT 38 THERE ARE 38 CITED REFERENCES AVAILABLE FOR THIS RECORD

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REFERENCE 7

AN 153:63818 CA

TI Radiation-curable resin compositions and their cured articles, coated



articles, optical films, optical lens, and optical disks, and manufacture of coated articles

IN Kawakami, Chigusa; Yamashita, Tsutomu  
PA Sanyo Chemical Industries, Ltd., Japan  
SO Jpn. Kokai Tokkyo Koho, 14pp.

CODEN: JKXXAF

DT Patent

LA Japanese

IPCI C08F0020-30 [I,A]; C08F0020-00 [I,C\*]; C08F0290-06 [I,A]; C08F0290-00 [I,C\*]

CC 38-3 (Plastics Fabrication and Uses)  
Section cross-reference(s): 37, 73, 74

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2010126670	A	20100610	JP 2008-304251	20081128
PRAI	JP 2008-304251		20081128		
AB	Radiation-curable resin compns. contain (A) aromatic ring-containing (meth)acrylates having 20-45% aromatic ring backbone carbons and (meth)acryloyl group equiv 150-220 g/equiv and (B) photopolymn. initiators and optionally, (C) aromatic ring-free polyfunctional (meth)acrylates with functionality $\geq 3$ . Coated articles having cured articles of the compns. on substrates, such as optical films, optical lens, or optical disks, are manufactured by applying the compns. at least on one surface of the substrates, followed by irradiating a radiation. Thus, a composition comprising 10 parts 2,2'-biphenyldimethanol diacrylate with aromatic ring backbone carbon content 45% and acryloyl group equiv 161, 90 parts Epikote 828 (bisphenol A diglycidyl ether) tetraacrylate with aromatic ring backbone carbon content 24% and acryloyl group equiv 151, and 2 parts Irgacure 184 (1-hydroxycyclohexyl Ph ketone) was sandwiched between 2 pieces of Lumirror S (PET film) then irradiated with UV, the PET films being parted, to give a 5- $\mu$ m thick test piece with refractive index at 25° 1.573. The composition was applied on a glass sheet, covered with Cosmoshine A 4300 (PET film) under pressure, and irradiated with UV to give a test piece showing cross-cut adhesion 0 peel/100 cuts and pencil hardness 3H.				
ST	UV curable acrylate resin coating optical film; lens optical UV curable acrylate; optical disk UV curable acrylate				
IT	Lenses Optical disks Optical films (UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)				
IT	Polyesters RL: TEM (Technical or engineered material use); USES (Uses) (UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)				
IT	Epoxy resins RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (acrylates; UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)				
IT	Epoxy resins RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (acrylic, crosslinked; UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)				

IT 947-19-3, Irgacure 184  
 RL: CAT (Catalyst use); USES (Uses)  
 (UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)

IT 24447-78-7P 55818-57-0P, Epikote 828 acrylate  
 RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)

IT 1228454-29-2P 1228454-31-6P  
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)

IT 223767-65-5P 1228454-30-5P 1228640-27-4P 1228640-99-0P  
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (crosslinked; UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)

IT 25038-59-9, Cosmoshine A 4300, uses  
 RL: TEM (Technical or engineered material use); USES (Uses)  
 (film, laminate with; UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)

## REFERENCE 8

AN 152:502755 CA  
 TI System and resin for rapid prototyping  
 IN Chapelat, Carole; Cherkaoui, Zoubair M.; Dobler, Beat; Frantz, Richard; Lagref, Jean-Jacques; Patel, Ranjana C.; Rhodes, Michael  
 PA Huntsman Advanced Materials (Switzerland) G.m.b.H., Switz.  
 SO PCT Int. Appl., 51pp.  
 CODEN: PIXXD2  
 DT Patent  
 LA English  
 IPCI B29C0067-00 [I,A]; G03F0007-038 [I,A]  
 IPCR B29C0067-00 [I,C]; B29C0067-00 [I,A]; G03F0007-038 [I,C]; G03F0007-038 [I,A]  
 CC 38-3 (Plastics Fabrication and Uses)  
 FAN.CNT 3

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2010043463	A1	20100422	WO 2009-EP61958	20090915
W:				
AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW				
RW:				
AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, SE, SI, SK, SM, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM				
WO 2010043274	A1	20100422	WO 2008-EP66634	20081202

W: AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW

RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MT, NL, NO, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM

PRAI EP 2008-18228 20081017

WO 2008-EP66634 20081202

AB The invention relates to a system and a resin relating to rapid prototyping. The system comprises (a) an apparatus for producing a three-dimensional object from a light-sensitive material, wherein input optics (IO) and output optics (OO) facilitates transmission of light emitted from an illumination source via individually controllable light modulators (LM) of spatial light modulator (SLM) to an illumination area (IA), wherein said (OO) enable focusing of the pattern of light from said (SLM) on said (IA); and (b) a resin composition comprising (A) an acrylate component with (B) a methacrylate component and (C) a photoinitiator.

ST three dimensional object prodn system prototyping

IT Polyurethanes

RL: TEM (Technical or engineered material use); USES (Uses)  
(methacrylates; system and resin for rapid prototyping)

IT Catalysts

(photochem.; system and resin for rapid prototyping)

IT Stabilizing agents

(system and resin for rapid prototyping)

IT 41637-38-1, Sartomer 348C

RL: TEM (Technical or engineered material use); USES (Uses)  
(SR 348C; system and resin for rapid prototyping)

IT 42594-17-2, Sartomer 833S

RL: TEM (Technical or engineered material use); USES (Uses)  
(SR 833S; system and resin for rapid prototyping)

IT 24650-42-8, Irgacure 651 75980-60-8, Lucirin TPO

RL: CAT (Catalyst use); USES (Uses)  
(system and resin for rapid prototyping)

IT 7803-49-8D, Hydroxy amine, N-nitroso complex

RL: MOA (Modifier or additive use); USES (Uses)  
(system and resin for rapid prototyping)

IT 24447-78-7, Sartomer 349 26403-58-7 26570-48-9, Sartomer 344

178153-95-2, Craynor CN 981 345295-25-2, Genomer 4205  
RL: TEM (Technical or engineered material use); USES (Uses)  
(system and resin for rapid prototyping)

RE.CNT 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD

(1) Chikaoka Satoyuki; US 6130025 A 2000 CAPLUS

(2) Dicon As; WO 0021735 A1 2000

(3) Michae, R; WO 2005092598 A1 2005 CAPLUS

(4) Smith Jeffrey M; US 6500378 B1 2002 CAPLUS

REFERENCE 9

AN 152:478559 CA

TI Adhesive composition and adhesion method

IN Hisha, Yuki; Yoda, Kimihiko; Oshima, Kazuhiro  
 PA Denki Kagaku Kogyo Kabushiki Kaisha, Japan  
 SO PCT Int. Appl., 22pp.

CODEN: PIXXD2

DT Patent

LA Japanese

IPCI C08L0033-00 [I,A]; C08K0003-10 [I,A]; C08K0003-00 [I,C\*]; C08K0005-07 [I,A]; C08K0005-17 [I,A]; C08K0005-00 [I,C\*]; C08L0009-02 [I,A]; C08L0009-00 [I,C\*]; C09J0004-02 [I,A]; C09J0005-00 [I,A]; C09J0011-06 [I,A]; C09J0011-02 [I,C\*]; C09J0109-02 [I,A]; C09J0109-00 [I,C\*]; C09J0133-04 [I,A]

IPCR C08L0033-00 [I,C]; C08L0033-00 [I,A]; C08K0003-00 [I,C]; C08K0003-10 [I,A]; C08K0005-00 [I,C]; C08K0005-07 [I,A]; C08K0005-17 [I,A]; C08L0009-00 [I,C]; C08L0009-02 [I,A]; C09J0004-02 [I,C]; C09J0004-02 [I,A]; C09J0005-00 [I,C]; C09J0005-00 [I,A]; C09J0011-02 [I,C]; C09J0011-06 [I,A]; C09J0109-00 [I,C]; C09J0109-02 [I,A]; C09J0133-04 [I,C]; C09J0133-04 [I,A]

CC 38-3 (Plastics Fabrication and Uses)

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2010041710	A1	20100415	WO 2009-JP67543	20091008
	W:	AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW			
	RW:	AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, SE, SI, SK, SM, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM			

PRAI JP 2008-262015 20081008

AB Disclosed is a high-speed-curing and moisture-resistant adhesive composition  
 Title composition comprises a first preparation comprising (A) a nitrile rubber, (B)

a (meth)acrylic composition, (C) a compound having an enal structure or (D) an amine compound, and (F) a radical polymerization initiator; and a second preparation

comprising (A) a nitrile rubber, (B) a (meth)acrylic composition, (D) an amine compound or (C) an enal compound, and (E) a compound containing copper.

ST adhesive compn two component; nitrile rubber acrylic polymer adhesive amine enal curing aid

IT Naphthenic acids

RL: MOA (Modifier or additive use); USES (Uses)

(copper salts; two-package adhesive composition and adhesion method)

IT Adhesives

(two-component; two-package adhesive composition and adhesion method)

IT Acrylic polymers

Nitrile rubber

RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)

(two-package adhesive composition and adhesion method)

IT 1709-70-2, 1,3,5-Trimethyl-2,4,6-tris(3,5-di-tert-butyl-4-hydroxybenzyl)benzene

RL: MOA (Modifier or additive use); USES (Uses)  
 (antioxidant; two-package adhesive composition and adhesion method)

IT 9003-18-3  
 RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)  
 (nitrile rubber; two-package adhesive composition and adhesion method)

IT 62-53-3, Aniline, uses 645-62-5, 2-Ethyl-2-hexenal 20543-04-8, Copper octanoate  
 RL: MOA (Modifier or additive use); USES (Uses)  
 (two-package adhesive composition and adhesion method)

IT 79-10-7D, Acrylic acid, polymers 79-41-4D, Methacrylic acid, polymers 3290-92-4D, Trimethylolpropane trimethacrylate, polymers 5888-33-5D, Isobornyl acrylate, polymers 7534-94-3D, Isobornyl methacrylate, polymers 9003-56-9, Acrylonitrile-butadiene-styrene copolymer 15625-89-5D, Trimethylolpropane triacrylate, polymers 24447-78-7D, polymers 24448-20-2D, polymers, uses 41637-38-1D, Bisphenol A-ethylene oxide adduct dimethacrylate, polymers 64401-02-1D, Bisphenol A-ethylene oxide adduct diacrylate, polymers 107080-92-2, Butadiene-methyl methacrylate-styrene graft copolymer 1200973-80-3  
 RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)  
 (two-package adhesive composition and adhesion method)

RE.CNT 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD

(1) Denki Kagaku Kogyo Kabush 1 ki Kaisha; WO 2008108273 A1 2008 CAPLUS  
 (2) Ministro Dell Universita' e Delia Ricerca Scientif 1 ca e Tecnologica; US 5283292 A1 1994 CAPLUS  
 (3) Ministro Dell Universita' e Delia Ricerca Scientif 1 ca e Tecnologica; EP 540098 A1 1994 CAPLUS  
 (4) Ministro Dell Universita' e Delia Ricerca Scientif 1 ca e Tecnologica; JP 6248238 A 1994  
 (5) Okura Industrial Co Ltd; JP 5125331 A 1993  
 (6) Okura Industrial Co Ltd; JP 2003165806 A 2003 CAPLUS

## REFERENCE 10

AN 152:466143 CA  
 TI Presensitized lithographic plates and manufacture of lithographic plates therefrom  
 IN Sasaki, Tomoya; Ohashi, Hidekazu  
 PA Fujifilm Corporation, Japan  
 SO Jpn. Kokai Tokkyo Koho, 63pp.  
 CODEN: JKXXAF

DT Patent  
 LA Japanese

IPCI G03F0007-027 [I,A]; G03F0007-004 [I,A]; G03F0007-00 [I,A]  
 IPCR G03F0007-027 [I,C]; G03F0007-027 [I,A]; G03F0007-00 [I,C]; G03F0007-00 [I,A]; G03F0007-004 [I,C]; G03F0007-004 [I,A]

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)  
 Section cross-reference(s): 35, 38

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2010079085	A	20100408	JP 2008-249138	20080926
PRAI	JP 2008-249138		20080926		

AB The presensitized lithog. plates have, on supports, photosensitive layers containing (A) compds. having groups chosen from R2R3C:CR1[C(:O)NR4],

- R5R5C:C(CONR7R8), and/or R10R11C:CR9[C(:O)N] (R1-R3, R5, R6, R9-R11 = H, alkyl, aryl; R4, R7, R8 = H, alkyl, aryl, aralkyl, alkenyl, heterocyclic), (B) polymerization initiators, (C) polymerizable compds. other than A, and (D) binder polymers, at A/C weight ratio 0.02-4. The presensitized lithog. plates are exposed and then developed by developers with pH 2-10 to remove unexposed parts. The presensitized lithog. plates have high development speed, printability, and initial and long-term soiling resistance.
- ST neg presensitized lithog plate acrylamide monomer ratio developability printability; soiling resistance neg presensitized lithog plate
- IT Polyoxyalkylenes  
 RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); TEM (Technical or engineered material use); PROC (Process); USES (Uses)  
 (acrylic, graft, binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)
- IT Polyvinyl butyrals  
 RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); TEM (Technical or engineered material use); PROC (Process); USES (Uses)  
 (binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)
- IT Lithographic plates  
 (neg.-working presensitized; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)
- IT Allylic compounds  
 RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)  
 (other monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)
- IT Lithography  
 (platemaking; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)
- IT Polyurethanes  
 RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); TEM (Technical or engineered material use); PROC (Process); USES (Uses)  
 (polyoxyalkylene-, block, acrylates, binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)
- IT Aromatic compounds  
 RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)  
 (vinyl, other monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)
- IT 28679-16-5, Trimethylhexamethylene diisocyanate  
 RL: RCT (Reactant); RACT (Reactant or reagent)  
 (2,2,4- and 2,4,4-mixture, in preparation of acrylamide monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)
- IT 1220748-62-8P 1220748-63-9P

RL: IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)

(acrylamide monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 959-52-4 1187-59-3 39573-27-8 143785-80-2 160432-07-5  
1045850-44-9 1220748-64-0 1220748-67-3

RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)

(acrylamide monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 170211-39-9 1140463-33-7

RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); TEM (Technical or engineered material use); PROC (Process); USES (Uses)

(assumed monomers, binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 59049-11-5

RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); PRPH (Prophetic); TEM (Technical or engineered material use); PROC (Process); USES (Uses)

(binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 9002-89-5 25086-15-1 65697-22-5 709037-26-3 915977-69-4  
1126184-48-2 1160246-70-7

RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); TEM (Technical or engineered material use); PROC (Process); USES (Uses)

(binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 1220748-58-2P 1220748-59-3P 1220748-60-6P 1220748-61-7P

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)

(in preparation of acrylamide monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 10029-04-6, Ethyl 2-(hydroxymethyl)acrylate

RL: RCT (Reactant); RACT (Reactant or reagent)

(in preparation of acrylamide monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 60506-81-2, SR 399

RL: PEP (Physical, engineering or chemical process); PRPH (Prophetic); TEM (Technical or engineered material use); PROC (Process); USES (Uses)

(other monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 1025-15-6, TAIC 24447-78-7 40220-08-4 41137-60-4 74389-53-0  
128738-52-3

RL: PEP (Physical, engineering or chemical process); TEM (Technical or

10/593,746

engineered material use); PROC (Process); USES (Uses)  
(other monomers; presensitized lithog. plates containing acrylamide  
monomers and other monomers at prescribed ratio in photosensitive  
layers and manufacture of lithog. plates therefrom)

IT 1220748-68-4

RL: PEP (Physical, engineering or chemical process); TEM (Technical or  
engineered material use); PROC (Process); USES (Uses)  
(presensitized lithog. plates containing acrylamide monomers and other  
monomers at prescribed ratio in photosensitive layers and manufacture of  
lithog. plates therefrom)

=> D HIS

(FILE 'HOME' ENTERED AT 15:03:12 ON 19 OCT 2010)

FILE 'REGISTRY' ENTERED AT 15:03:23 ON 19 OCT 2010

L1 0 S 64404-02-4  
L2 6 S SARTOMER 349  
L3 0 S SARTOMER 349/CRN  
L4 1 S SARTOMER 349/CN

=> S EBECRYL 8402

2092 EBECRYL

238 8402

L5 76 EBECRYL 8402  
(EBECRYL(W) 8402)

=> S EBECRYL 8402/CN

L6 1 EBECRYL 8402/CN

=> D

L6 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2010 ACS on STN  
RN 183449-62-9 REGISTRY  
ED Entered STN: 27 Nov 1996  
CN Ebecryl 8402 (CA INDEX NAME)  
OTHER NAMES:  
CN EB 8402  
CN EBC 8402  
CN Ebecryl EB 8402  
ENTE An aliphatic urethane acrylate (Cray Valley)  
MF Unspecified  
CI PMS, COM, MAN  
PCT Manual registration  
SR CA  
LC STN Files: CA, CAPLUS, TOXCENTER, USPAT2, USPATFULL

\*\*\* STRUCTURE DIAGRAM IS NOT AVAILABLE \*\*\*

38 REFERENCES IN FILE CA (1907 TO DATE)

9 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA

38 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> D HIS

(FILE 'HOME' ENTERED AT 15:03:12 ON 19 OCT 2010)



10/593,746

FILE 'REGISTRY' ENTERED AT 15:03:23 ON 19 OCT 2010

L1	0 S 64404-02-4
L2	6 S SARTOMER 349
L3	0 S SARTOMER 349/CRN
L4	1 S SARTOMER 349/CN
L5	76 S EBECRYL 8402
L6	1 S EBECRYL 8402/CN

=> LOG Y

COST IN U.S. DOLLARS	SINCE FILE	TOTAL
	ENTRY	SESSION
FULL ESTIMATED COST	50.63	50.85
DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)	SINCE FILE	TOTAL
	ENTRY	SESSION
CA SUBSCRIBER PRICE	-0.80	-0.80

STN INTERNATIONAL LOGOFF AT 15:05:17 ON 19 OCT 2010